Time Stamp	2005/02/16 09:27	2005/02/16 09:29	2005/02/16 09:29	2005/02/16 11:39	2005/02/16 11:44	2004/12/22 08:16	2004/12/22 10:53
Plurals	N _O	NO O	NO	NO	OFF	NO	NO
Default Operator	S.	S.	NO.	R	R	SO	SO.
DBs	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
Search Query	pair same (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane) same (first adj (surface link connect\$3 contact\$3)) same (second adj (surface link connect\$3 contact\$3))	(pair near2 (short open load) near2 circuit) same (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane) same (first adj (surface link connect\$3 contact\$3) same (second adj (surface link connect\$3 contact\$3))	IS and (pair near2 (short open load) near2 circuit)	I7 and @ad<"20030923"	("5047752").PN.	(324/601.ccls.) and @ad<"20030923"	(324/600.ccls.) and @ad<"20030923"
Hits	4380	H	w	4		418	114
Ref #	51	97	77	87	L13	S1	22

S3	9	(("6348804") or ("5407752") or ("4858160")).PN.	US-PGPUB;	R	H-O	2004/12/22 10:30
			DSFAT, EPO; JPO; DERWENT; IBM_TDB			
S4	2	("20040070405").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	g	OFF	2004/12/22 10:30
SS	17	impedance adj standard adj substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	N O	2004/12/22 13:25
98	41	S5 and @ad<"20030923"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO.	N O	2004/12/22 13:27
S7	2	("4,697,143").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	R	OFF	2004/12/22 11:22
88	3406	((impedance adj standard adj (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)) ISS)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	R	NO	2004/12/22 13:34
83	3237	S8 and @ad<"20030923"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	R	NO	2004/12/22 13:37

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ON 2004/12/22 15:09	ON 2005/02/16 09:23	ON 2004/12/22 13:46	ON 2004/12/22 13:46	ON 2004/12/22 15:04	ON 2004/12/22 13:52	ON 2004/12/22 14:33
8	8	8	8	8	8	8
US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
S9 and (oscill\$7 VNA (vector adj network adj anal\$5)) near3 (\$2adjust\$ calibrat\$5)	impedance adj standard adj (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane)	S11 and @ad<"20030923"	(oscill\$7 VNA (vector adj network adj anal\$5)) near3 (\$2adjust\$ calibrat\$5)	S13 and @ad<"20030923"	S14 and impedance adj standard adj (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane assembly unit system device apparatus machine mechanism section station means module set instrument tool circuit equipment)	S14 and impedance adj2 (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane circuit)
13	18	15	21871	20561	7	586
S10	S11	S12	S13	S14	515	S16

S17	45	S1 and impedance adj2 (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane circuit)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2004/12/22 15:00
S18	20	S2 and impedance adj2 (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane circuit)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR S	N _O	2004/12/22 15:03
S19	168	S16 and electrical\$3 near2 (connect\$3 contact\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	N O	2004/12/22 14:35
820	141	S19 and first same second	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO	2004/12/22 14:37
521	9	S19 and (first adj (surface link connect\$3 contact\$3)) same (second adj (surface link connect\$3 contact\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO O	2004/12/22 15:05
225	17689	(surface link connect\$3 contact\$3) same impedance adj2 (substrate material \$5film coat\$3 layer sheet pad wafer film lamina level plane circuit)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO O	2004/12/22 15:03
S23	16924	S22 and @ad<"20030923"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO.	NO	2005/02/16 09:29

S24	899	S23 and (first adj (surface link connect\$3 contact\$3)) same (second adj (surface link connect\$3 contact\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	SO.	NO	2004/12/22 15:05
525	10	S24 and (oscill\$7 VNA (vector adj network adj anal\$5)) near3 (\$2adjust\$calibrat\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	N O	2004/12/22 15:37
S26	2	S2 and (oscill\$7 VNA (vector adj network adj anal\$5)) near3 (\$2adjust\$calibrat\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	NO	2004/12/22 15:37
S27	80	S1 and (oscill\$7 VNA (vector adj network adj anal\$5)) near3 (\$2adjust\$calibrat\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	& S	N O	2004/12/22 15:38
828	H	S26 and (surface link connect\$3 contact\$3) same via	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	S.	N O	2004/12/22 15:44
825	33	S27 and (surface link connect\$3 contact\$3) same via	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	& S	N O	2004/12/22 15:39
530	70699	via and calibration	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	NO	2004/12/22 15:45

531	386	Rus	US-PGPUB;	æ	NO NO	2004/12/22 15:45
 			USPAT;			·
			EPO; JPO;			
			DERWENT;			
			IBM_TDB			
S32	57	S30 and S31	US-PGPUB;	发	NO	2004/12/22 15:45
1			USPAT;			
			EPO; JPO;			
			DERWENT;			
			IBM_TDB			
533	52	S32 and @ad<"20030923"	US-PGPUB;	S S	NO	2004/12/22 15:45
			USPAT;			
			EPO; JPO;			
			DERWENT;			
			IBM_TDB			